ATS-Furnace Series Vacuum Furnace for Display Materials Purification



Special Features

- Economic standard sputter system for R&D and small mass production
- ◆ Two tiltable 4" sputter guns and one extra sputter gun port
- Quartz tube conveniently exchangeable
- ◆ Plug system movable in x, y, z direction
- Process range 400 ~ 900℃
- Operated by PLC touch screen
- Applications display materials purification differential evaporation of organic materials

Wafer capacity 100 × 8"

Others

- Average throughput Up to 30,000 wafers per year
- Dimension $2,500L \times 1,500H \times 6,00W \text{ (mm³)}$
- Power: AC 220V, 2 phase

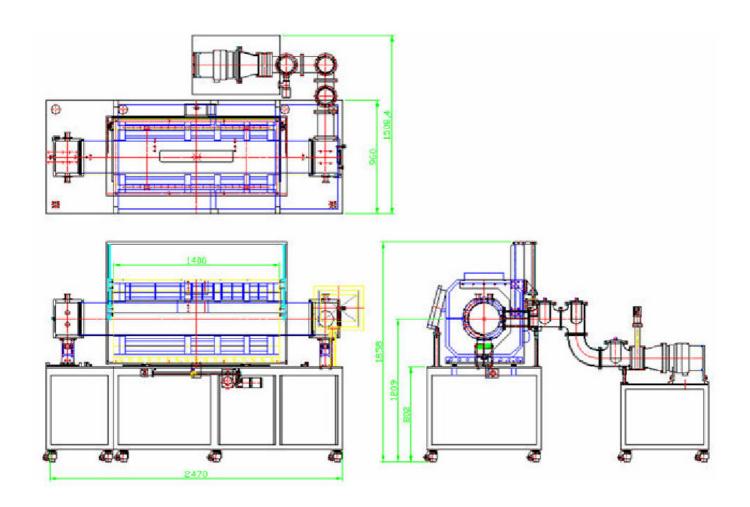
Gas: N₂/Ar Heater: KT APM molding heater (kanthal)

> (heating rate: 10°C/min, max. temp.:1000℃, deviation: negligible)

Pump: rotary(600I/min) & turbo(350I/s)



♦ Layout



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